EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	861	laminar adj airflow	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 11:56
S1	1	("6248171").PN.	US-PGPUB; USPAT	OR	OFF	2006/05/10 05:14
S2	1	("6669779").PN.	US-PGPUB; USPAT	OR	OFF	2006/05/10 05:21
S3	150992	(develop or developer or developed or developing or development).ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:22
S4	535733	(develop or developer or developed or developing or development).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:22
S5	2	S1 or S2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:22
S6	563042	S3 or S4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:23
S7	127500	(lithographic or photopolymer or photoresist or resist or (printig adj plate)) same (develop or developer or developed or developing or development)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:24
S8	42815	S6 and S7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:24

S9	2467	((develop or developer or developed or developing or development) same (liquid or fluid or solution or compostion) same (plural$ or multiple)) same ((surface or top or layer) adj3 (wafer or photopolymer or photoresist or resist or circuit or semiconductor or plate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 05:33
S10	232	S8 and S9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07
S11	9	fine adj disbursement	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 11:56
S12	70153	mist	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:06
S13	70162	S11 or S12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:06
S14	150992	(develop or developer or developed or developing or development).ti.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07
S15	535733	(develop or developer or developed or developing or development).ab.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07
S16	563042	S14 or S15	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07

S17	127500	(lithographic or photopolymer or photoresist or resist or (printig adj plate)) same (develop or developer or developed or developing or development)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07
S18	42815	S16 and S17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07
S19	2467	((develop or developer or developed or developing or development) same (liquid or fluid or solution or compostion) same (plural$ or multiple)) same ((surface or top or layer) adj3 (wafer or photopolymer or photoresist or resist or circuit or semiconductor or plate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:07
S20	232	S18 and S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:08
S21	10	S13 and S20	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:10
S22	44	S13 and S19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:11
S23	34	S22 not S21	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:13
S24	167	S13 and S18	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 09:14

S25	167	S24 not S23	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/05/10 10:39